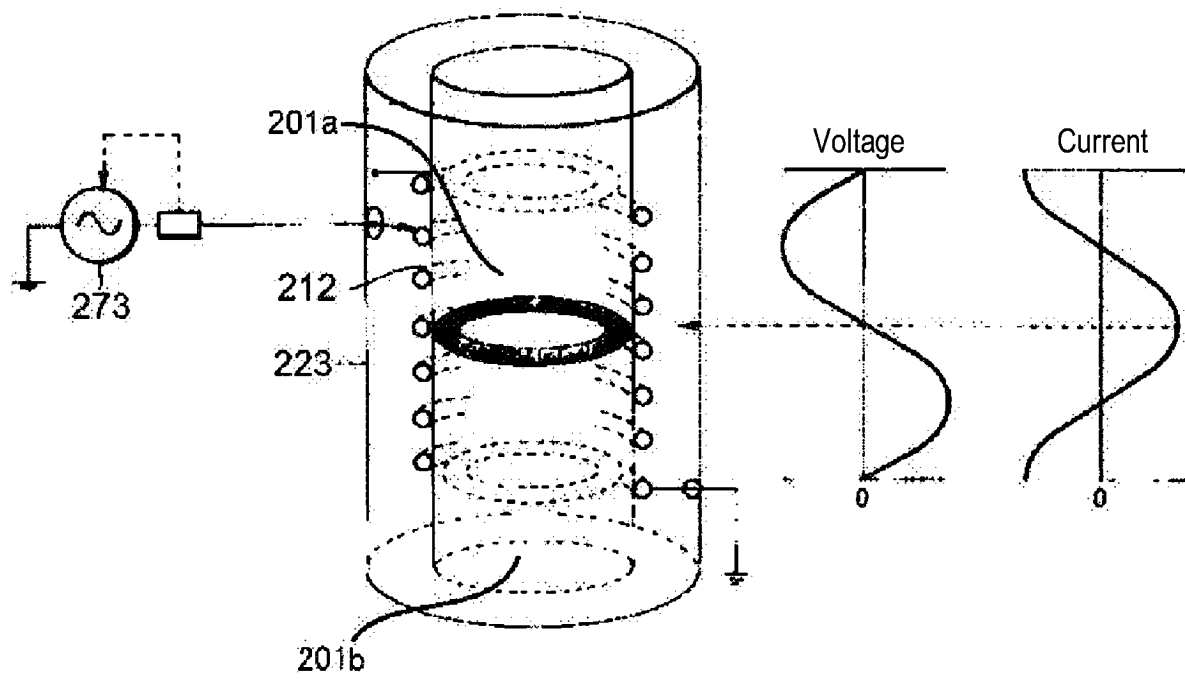


FIG. 2



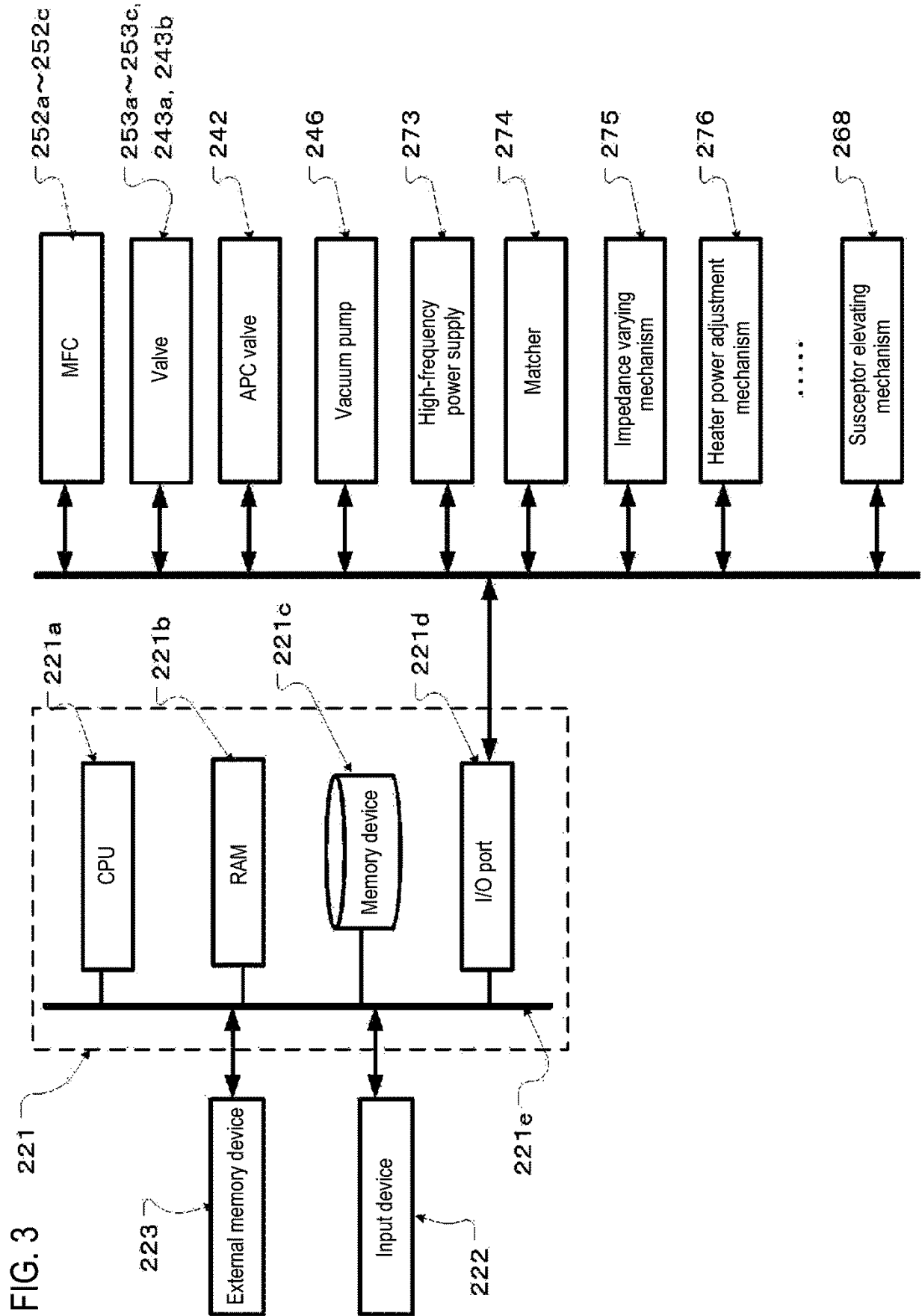


FIG. 4

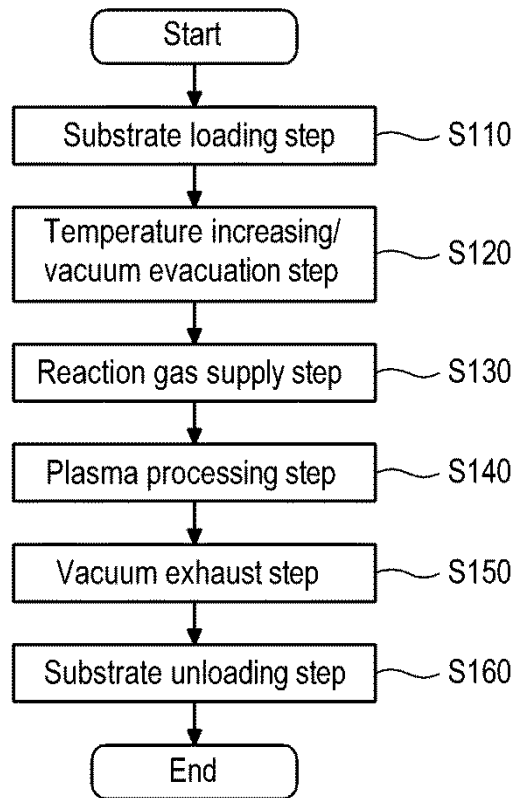


FIG. 5

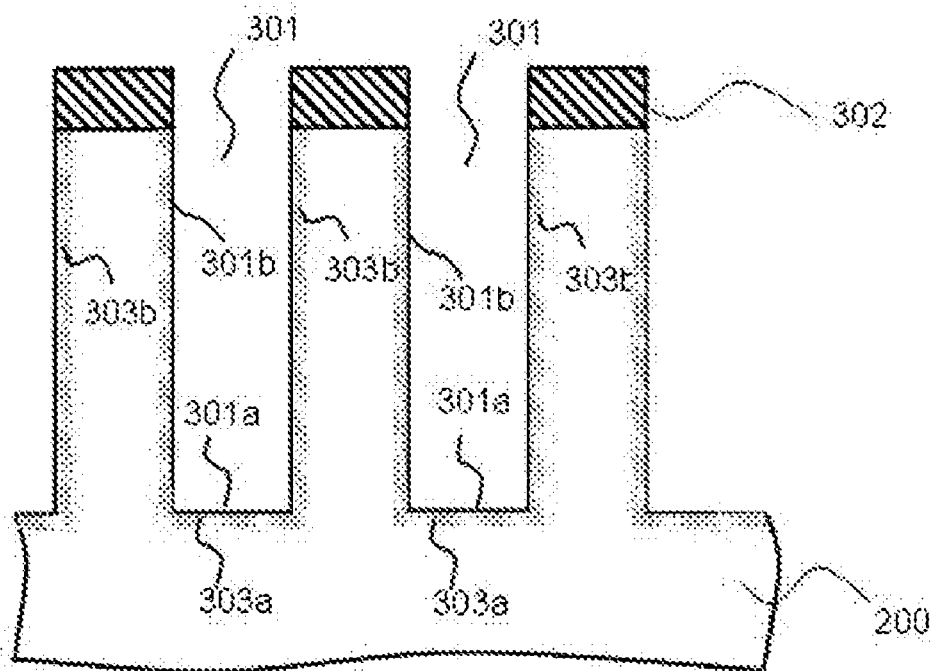


FIG. 6

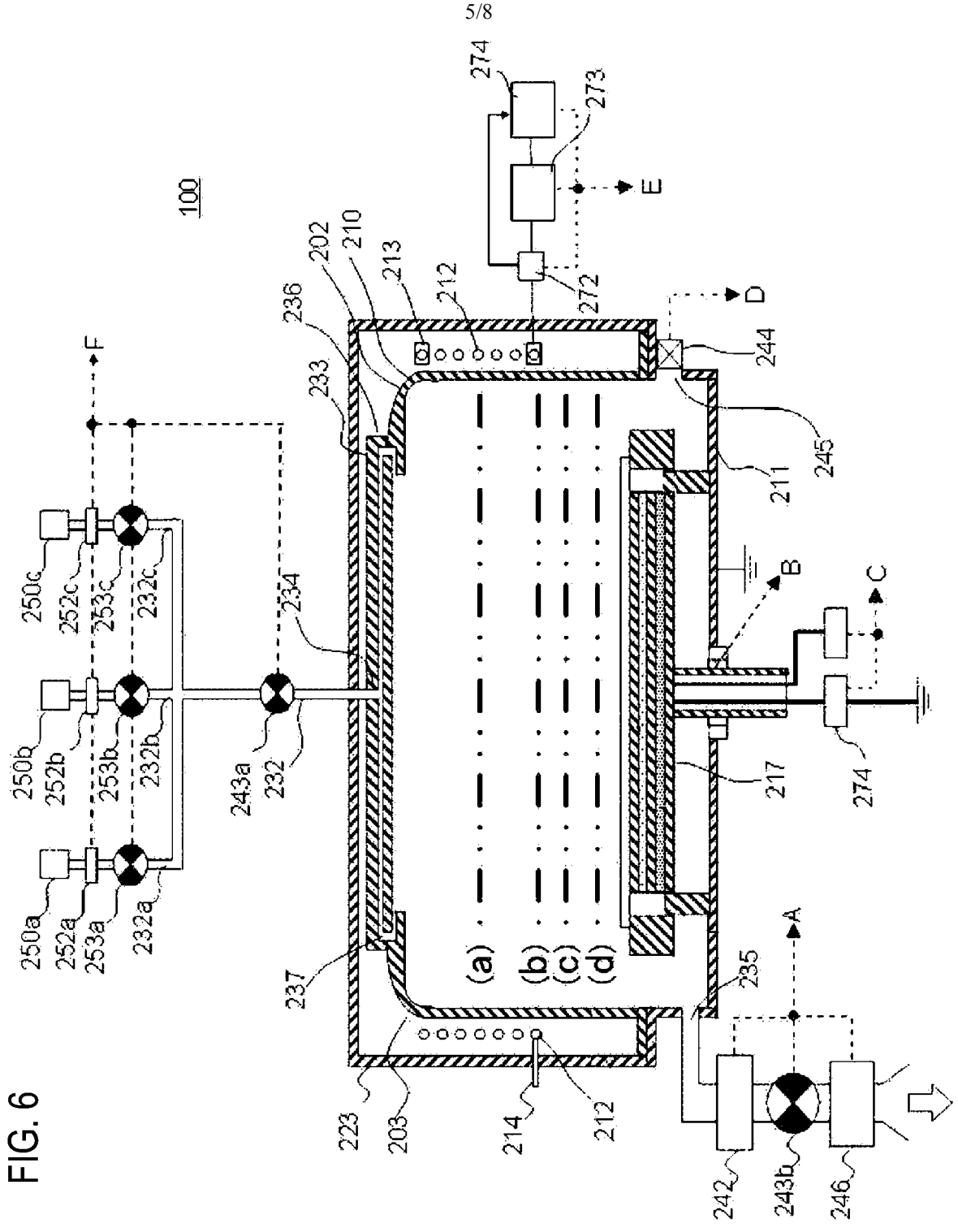


FIG. 7

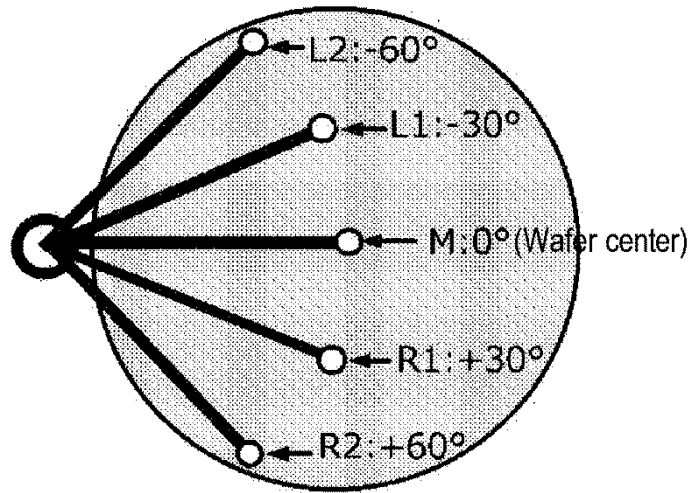


FIG. 8

Electron density at each measurement position

	Horizontal position (angle from center)				
	L2(-60°)	L1(-30°)	M(0°)(Center)	R1(+30°)	R2(+60°)
(a) Coil center (100 mm from coil lower end)	8.68E+08	1.08E+08	6.45E+07	1.33E+08	9.69E+08
(b) Coil lower end (reference position)	2.37E+08	5.28E+07	6.82E+07	8.25E+07	6.26E+08
(c) 38 mm from coil lower end	9.76E+07	5.03E+07	1.27E+08	1.04E+08	1.17E+08
(d) 88 mm from coil lower end	1.63E+07	4.35E+07	5.99E+07	7.28E+07	4.36E+07

Unit: [per cm³]

[Measurement condition]

- Gas flow rate : O₂=950[sccm], H₂=50[sccm]
- Chamber pressure : 150[Pa]
- RF power : 3500[W]
- Wafer mounted 50 mm downward from height position (d)

FIG. 9

